

<b>INFORMATION DISCLOSURE CITATION</b> <i>(Use several sheets if necessary)</i>				ATTY DOCKET NO. PIS920030377	SERIAL NO.		
				Huang et al.			
				FILING	GROUP		
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
S JL	2002/0081520	06-27-02	Sooriyakumaran et al.	430	270.1		
	2001/0036594	11-01-01	Kozawa et al.	430	270.1		
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<b>FOREIGN PATENT DOCUMENTS</b>							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
S JL		"Effects of resist components on image spreading during postexposure bake of chemically amplified resists", Hinsberg et al. Proceedings of SPIE Vol. 3999 (2000), ppgs. 148-160					
S JL		"Determination of coupled acid catalysis-diffusion processes in a positive-tone chemically amplified photoresist" Houle et al. Journal Vac. Sci. Technology B 18 (4) Jul/Aug 2000, ppgs. 1874-1885					
S JL		"Direct measurement of the reaction front in chemically amplified photoresists" Lin et al. Science, Vol. 297, 19 July 2002, ppgs. 372-375					
S JL		"Modeling and simulations of a positive chemically amplified photoresist for x-ray lithography", Krasnoperova et al., Journal Vac. Sci. Technology B 12 (6) Nov/Dec 1994, ppgs. 3900-3904					
EXAMINER				DATE CONSIDERED		3/2/05	
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